

**The CapSpin system is a tool for spin processing of glass plates and photomasks with dimensions of up to 9" x 9" and higher, configured to customers applications.**

CapSpin Photomask Cleaner  
CapSpin Photomask Processor

## Cleaner Applications

- **SPM Cleaning** with chemicals H<sub>2</sub>SO<sub>4</sub>, H<sub>2</sub>O<sub>2</sub>
- **SC-1 Cleaning** with chemicals NH<sub>4</sub>OH, H<sub>2</sub>O<sub>2</sub> and H<sub>2</sub>O
- **Brush Cleaning**
- **High Pressure Cleaning** from 25 - 200 bar
- **Megasonic Cleaning**

## Processor Applications

- **Photoresist Develop** for aqueous resists (i. e. AZ 351 B)
- **Chrome Metal Etch** binary spray nozzles (ammonium-Cer-Nitrate)
- **Resist Strip with spray nozzles** i.e. with KOH
- **DI-Water Rinse** with top- and backside rinse nozzles
- **Spin Dry** supported by IPA, Nitrogen, hot DI-water

## Tool Concept

**The CapSpin is an automated wet cleaning / wet processor system for up to 9" glass plates and photomasks. It offers robotic or manual handling, configured to customers applications.**

- Large open process chamber, symmetrical exhaust and uniform airflow
- Extended diameter in process area for optimum process environment
- Vertical movement of chuck for loading and unloading of the masks
- Different process levels avoiding cross contamination
- Stationary nozzles, nozzles mounted on motor driven dispense arm
- Fine adjustment of distance to mask for optimum process condition
- Precise temperature control of process media
- Advanced process control



### Systems available with

- Robotic handling
- Manual handling
- Various substrate sizes

4" x 4"  
5" x 5"  
6" x 6"  
6" x 9"

and others

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